

**S/N: 09/047,944**

**PATENT**

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Applicant: Moshe Finarov

Examiner: E. Morgan

Serial No: 09/047,944

Group Art Unit: 3723

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(P-743-US1)

Title: APPARATUS FOR OPTICAL INSPECTION OF WAFERS DURING  
POLISHING

San Jose, California  
November 2, 1998

**AMENDMENT AND INTERVIEW SUMMARY**

Commissioner for Patents and Trademarks  
Washington, DC 20231

Sir:

This paper is submitted in response to the First Official Action of June 1, 1998.

Please amend the Patent Application as follows.

**IN THE SPECIFICATION:**

At page 8, line 17, delete "14" and replace it with - -13- -.

**IN THE DRAWINGS:**

Please amend Fig. 13, submitted herewith.

**IN THE CLAIMS:**

Please amend claims 17-19 as below.

17. (Once Amended). A [polisher having the ability to measure the thickness  
of a top layer of a wafer, the polisher] wafer polishing apparatus comprising: